

ZrO₂

TANTALUM Oxide SPUTTERING TARGET

Tantalum oxide is an inorganic chemical compound with a chemical formula of Ta₂O₅. It is mainly used to produce capacitors which can be found in auto electronics, cell phones, and tools. Tantalum oxide can also be found in the glass for camera lenses. It is evaporated under vacuum to form films for the fabrication of semiconductors, optoelectronic devices, and fuel cells.

Quick Facts

Product	:	Tantalum Sputtering Target
Stock No	:	NS6130-10-1329
CAS	:	1324-61-0
Backing Plate	:	(As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1329	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
ZrO ₂	441.89g/mol	1872°C



Follow us:



| www.nanoshel.com | sales@nanoshel.com

INTELLIGENT MATERIALS PVT LTD

Derabassi
Punjab (140507)
INDIA

+91 9779 550077, 9779238252

NANOSHEL UK LIMITED

Chapel House,
Chapel St Cheshire,
CW12 4AB United Kingdom

+44 (0) 74 105 488, +44 203 137 5187

NANOSHEL LLC

3422 Old Capitol Suit
1305 Wilmington DE - 19808
United States

+1 646 470 4911

ISO 9001:2015
CERTIFIED COMPANY



19ZAZGO1274G

20ZICE4588M

20ZICE4589C

High Purity
SPUTTERING
TARGET